

# Visualization of Structure and Composition During Photocathode Growth

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Brookhaven National Lab/SUNY Stony Brook

SUNY Stony Brook

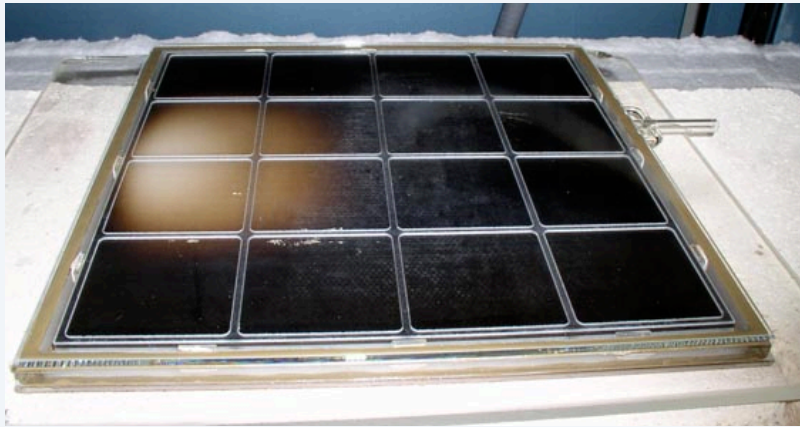
SUNY Stony Brook

Brookhaven National Lab.

BESSY/Helmholtz-Gesellschaft

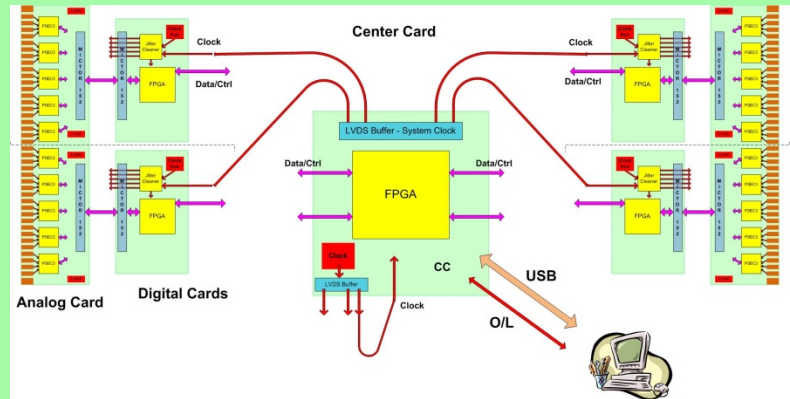
# The 4 `Divisions' of LAPPD

## Hermetic Packaging



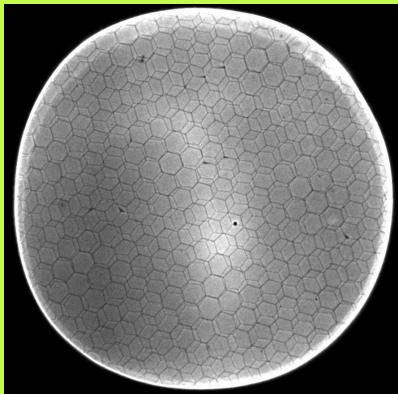
See Bob Wagner's talk

## Electronics/Integration



See Henry Frisch's Talk

## MicroChannel Plates

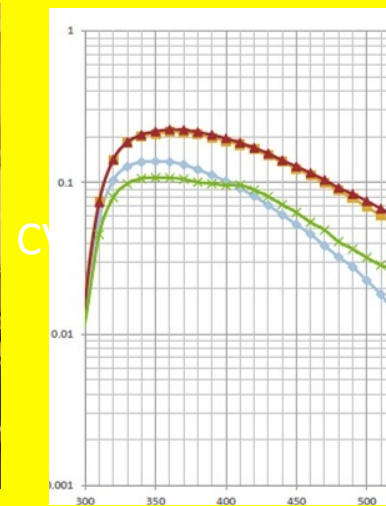


See (hear) Bob Wagner's & Ossy Siegmundtalk

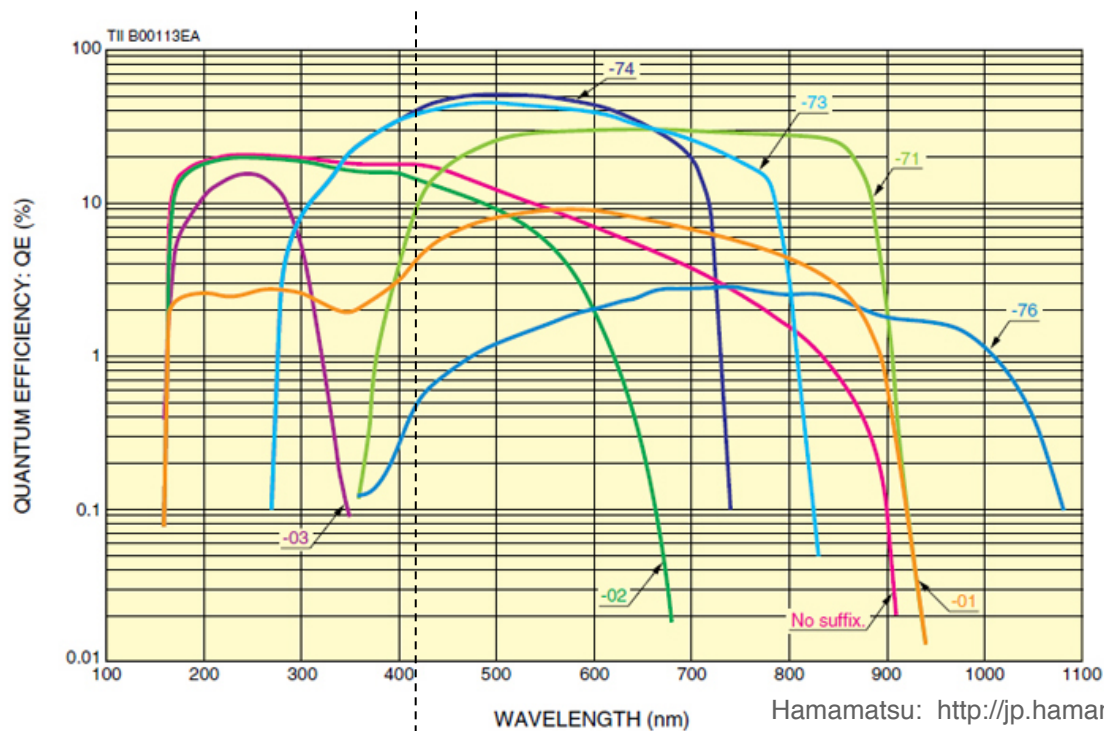
## Photocathodes



This Talk



# What is a Photocathode?



Suffix	Photocathode	Input Window
-71	GaAs	Borosilicate Glass
-73	Enhanced Red GaAsP	Borosilicate Glass
-74	GaAsP	Borosilicate Glass
-76	InGaAs	Borosilicate Glass
Non	Multialkali	Synthetic Silica
-01	Enhanced Red Multialkali	Synthetic Silica
-02	Bialkali	Synthetic Silica
-03	Cs-Te	Synthetic Silica

- Various cathodes are feasible
  - Only semiconductor cathodes are useful for detection applications
  - Multi-alkali are the the only cathodes available at 400nm and polycrystalline
- Focus on Multi-alkali cathodes:
  - Cost efficient thin film technology
  - Low dark current
  - High conductivity
  - Relative robust (unclear what destroys the cathode)

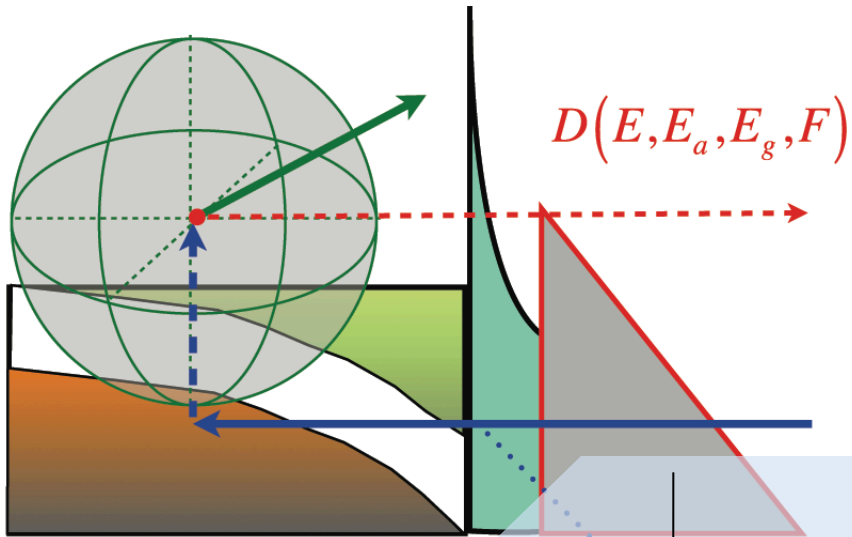
# Goals and Activities

- Goals of the project
  - High Quantum Efficiency
    - Unclear what number but larger 50%
    - Response optimized at 400nm
    - First approach: low count rate application
  - High production yield
    - Low variation from batch to batch
    - Independent from “personal experiences” ; can be performed by control system
  - Low production cost
    - Short production cycle
    - Large parameter-acceptance
- Activities:
  - Basic sciences:
    - General understanding and modeling of growth process
    - Pre-selection of optimization parameter space
    - Recipe suggestions
  - Engineering
    - Reproducibility of evaporators
    - Development of process-control parameters
    - Designing process environment for optimized recipe

# Basic Sciences

- Visualizing what happens during the growth:
  - Scattering experiments have proven very power full
  - To do:
    - Learning how to analyze data (especially diffuse scattering)
    - Automatic data analysis with automatic creation of rate constants
    - Improving evaporator system to allow “arbitrary” recipe
    - Reconstruction of spatial model
    - Simulation of thin film growth
- What we need from the material:
  - Single crystal in surface normal direction
    - Unclear what is the best lateral size
    - Minimizing impurity scattering (avoiding solid state alloying?)
  - Creating electric fields
    - Substrate effects
    - Doping
    - Layered structures
  - Influence of surface states on dark current

# What Determines the Quantum Efficiency?



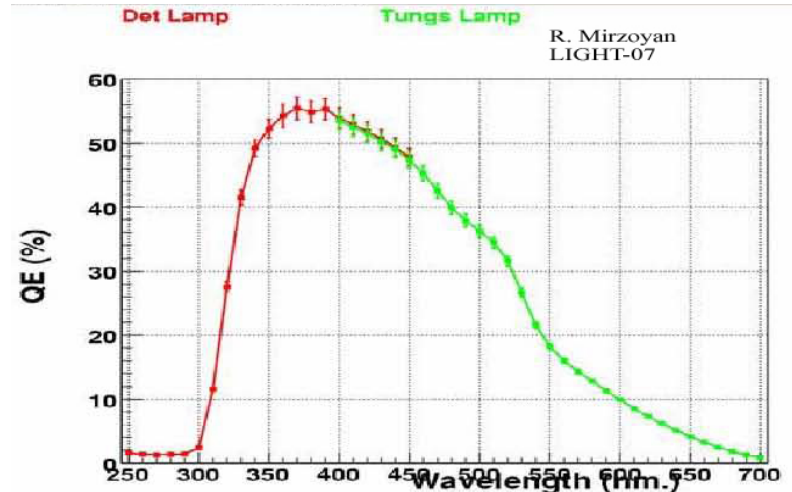
Semiconductor

$$\frac{\hbar^2 k_{\perp}^2}{2m} > E_T = E_f + \phi$$

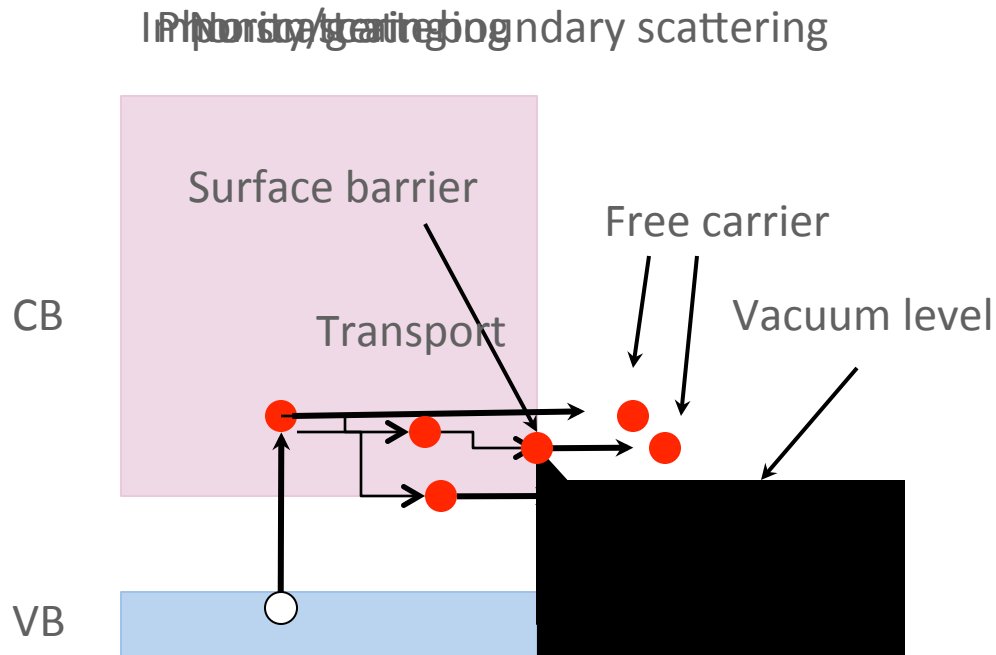
$$QE(\nu) \propto (\hbar\nu - \phi)^2$$

- In perfect Material (multi-alkali)
  - Original photoelectron direction is random (due to s-p character of valence & conduction band).
  - Cone determined by kinetic energy and surface barrier.
  - Phonon scattering helps to increase slightly the escape probability.

## Maximal QE ~ 60%?



# Why does Materials Quality Play a Role?

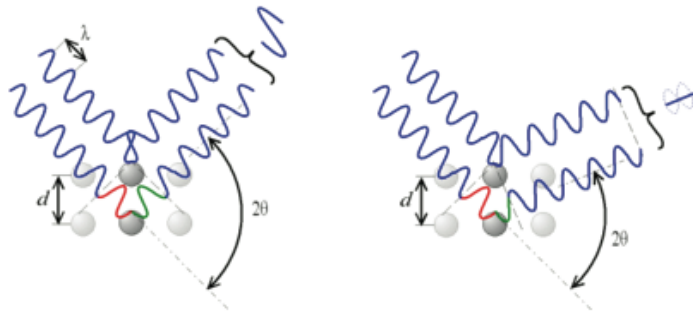


Material composition determines:

- Band gap
- Work function
- Surface barrier

- Description of cathode functionality in Spicer-Three-Step-Model
  - Absorption, Transport, emission
- No scattering:
  - Photon energy is converted in kinetic energy of photoelectron
  - Electron will be emitted (as long as momentum perpendicular to surface is large enough)
- Phonon scattering
  - Small energy loss per scattering event
  - Randomizing direction
- Impurity/grain boundary scattering
  - Large energy loss per scattering event
  - Small probability to escape!

# X-ray Scattering: A Perfect In-Situ Tool to Analyze Composition, Structure, and Chemistry!

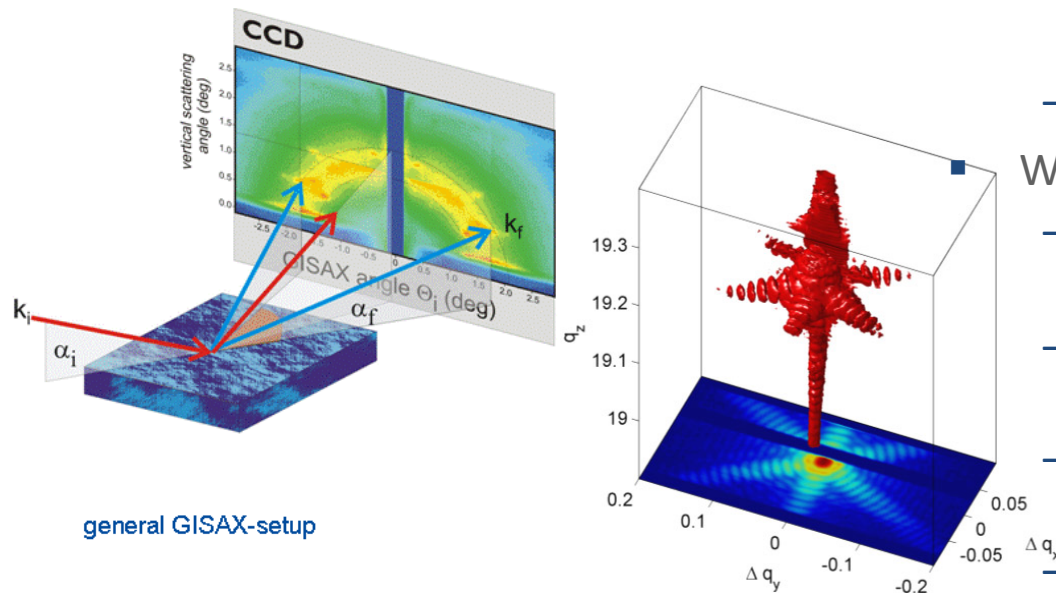


- The elementary process
  - Each atom scatters X-rays in  $4\pi$
  - An ensemble of atoms:
    - Crystalline form produces “bragg”-peaks
    - Amorphous materials produce a “Pair-Distribution-Pattern”

- Single wavelength diffraction:
  - Single crystal produces typically only one reflection (or none)
  - A powder of single crystals produce Rings

What information is in the diffraction pattern

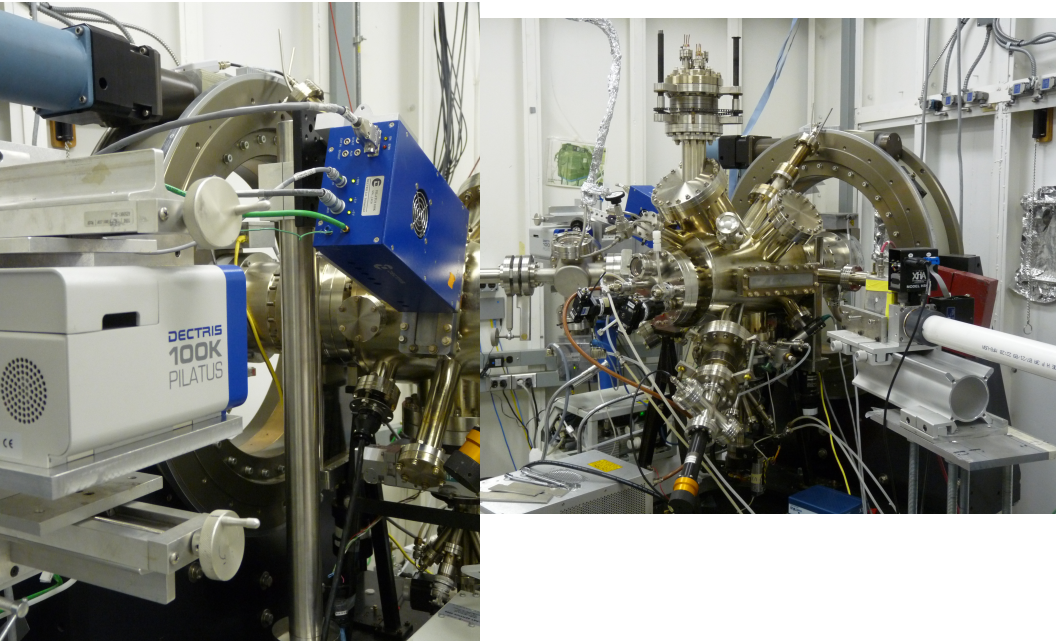
- 2-Theta position is a measure for the lattice-plane distance
- Phi-position reflects orientation of the crystallites
- Width and shape of the reflection reflects crystallite size and/or strain of the crystal
- Detailed analysis of peak-shapes will produce electron-density map of sample



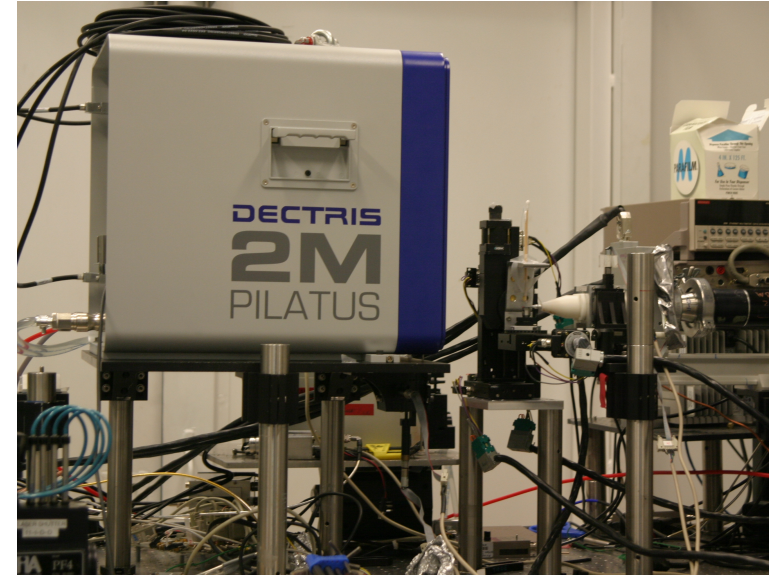


# The Experimental Setup

## BNL

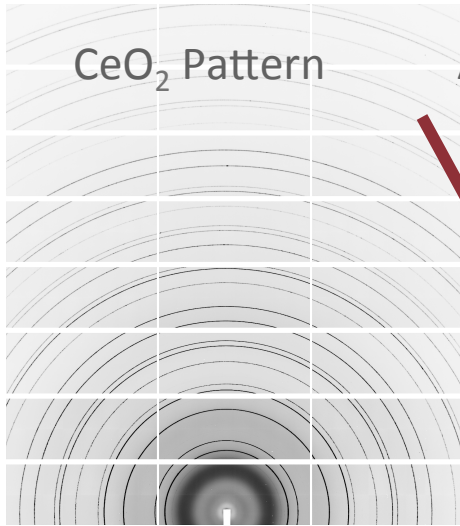


## ANL

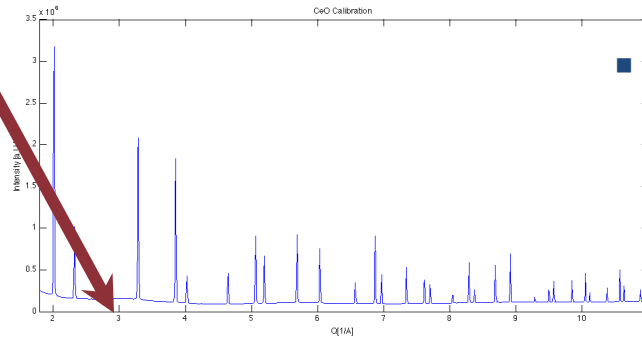


- Experiments take place at BNL/NSLS I and ANL/APS
- Currently no dedicated insitu chamber available
- However: New chamber for BNL in commissioning and transportable evaporator under design

# Data-Processing

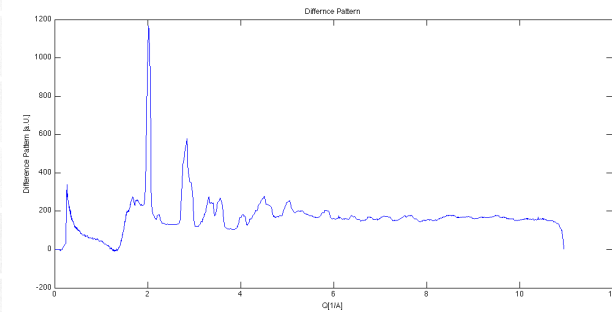
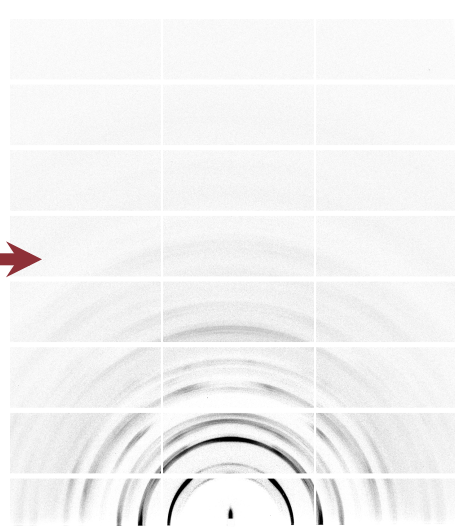
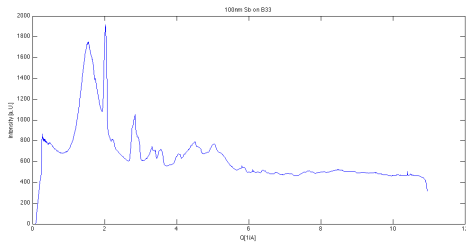
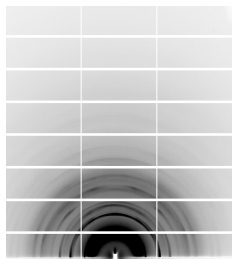
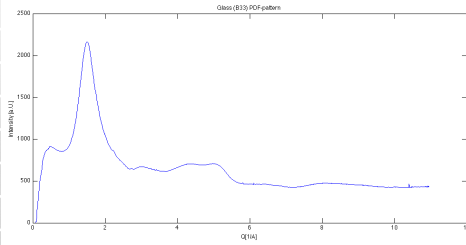


Azimuthal Integration and fit of peak positions

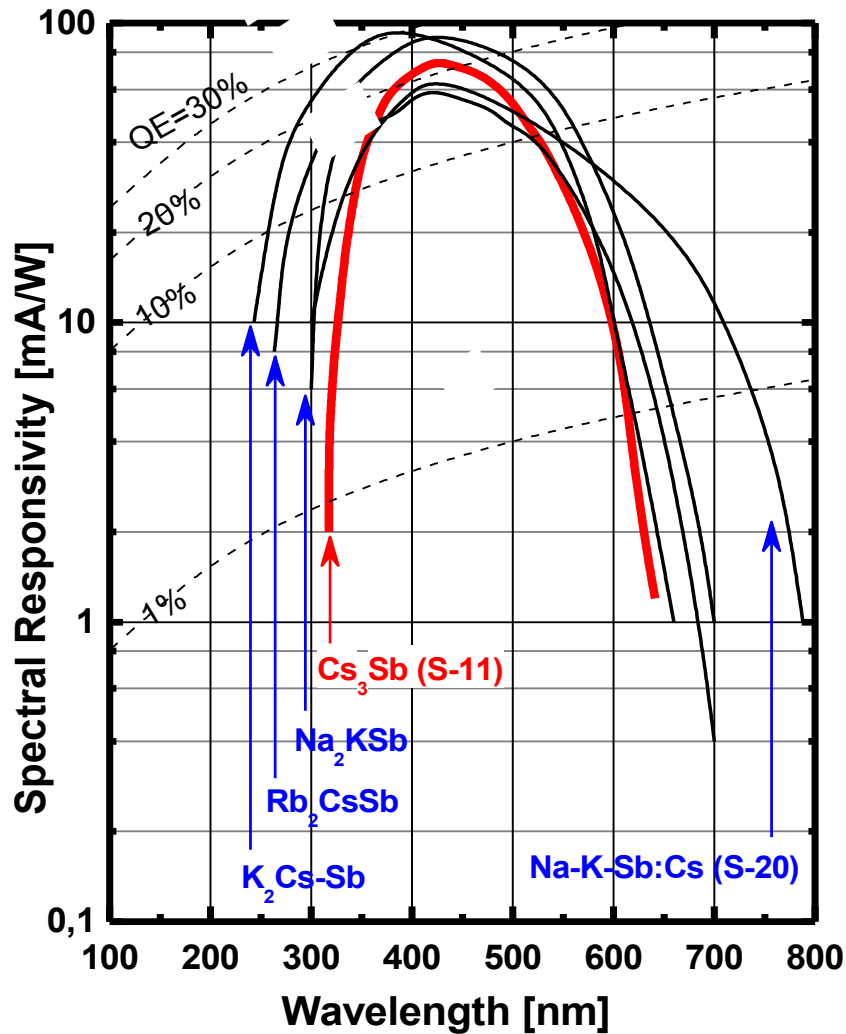


## Data-Analysis:

- Calibration with known standard (CeO<sub>2</sub>)
- “Empty”-pattern (B33)
- Sb-on B33 pattern
- Result: Difference showing only Sb-film and changes on glass-substrate



# A Closer Look to Multi-Alkali Cathodes



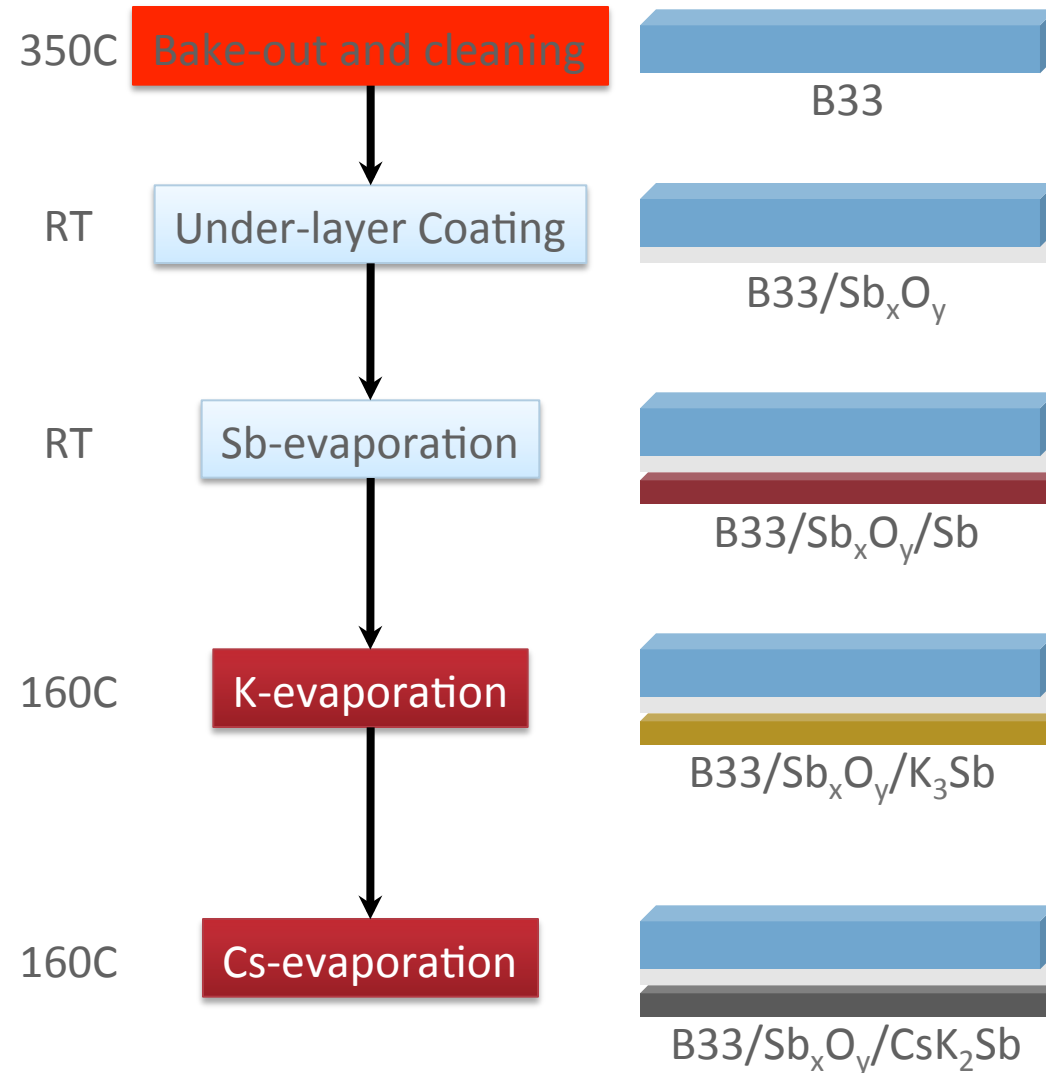
## Periodic Table of the Elements

1	2											13	14	15	16	17	18				
1 H 1.00794	2 He											31 Ga	32 Ge	33 As	34 Se	35 Br	36 Kr				
3 Li 6.941	4 Be	11 Na	12 Mg	19 K	20 Ca	21 Sc	22 Ti	23 V	24 Cr	25 Mn	26 Fe	27 Co	28 Ni	29 Cu	30 Zn	49 In	50 Sn	51 Sb	52 Te	53 I	54 Xe
5 Rb	6 Sr	37 Y	38 Zr	41 Nb	42 Mo	43 Tc	44 Ru	45 Rh	46 Pd	47 Ag	48 Cd	79 Au	80 Hg	81 Tl	82 Pb	83 Bi	84 Po	85 At	86 Rn	87 Fr	88 Ra
7 Fr	8 Ra	89 + Ac	104 Rf	105 Ha	106 106	107 107	108 108	109 109	110 110												

- Typical compound:  $\text{SbA}_3$
- A: (Li), Na, K, Cs
- Various combinations are possible

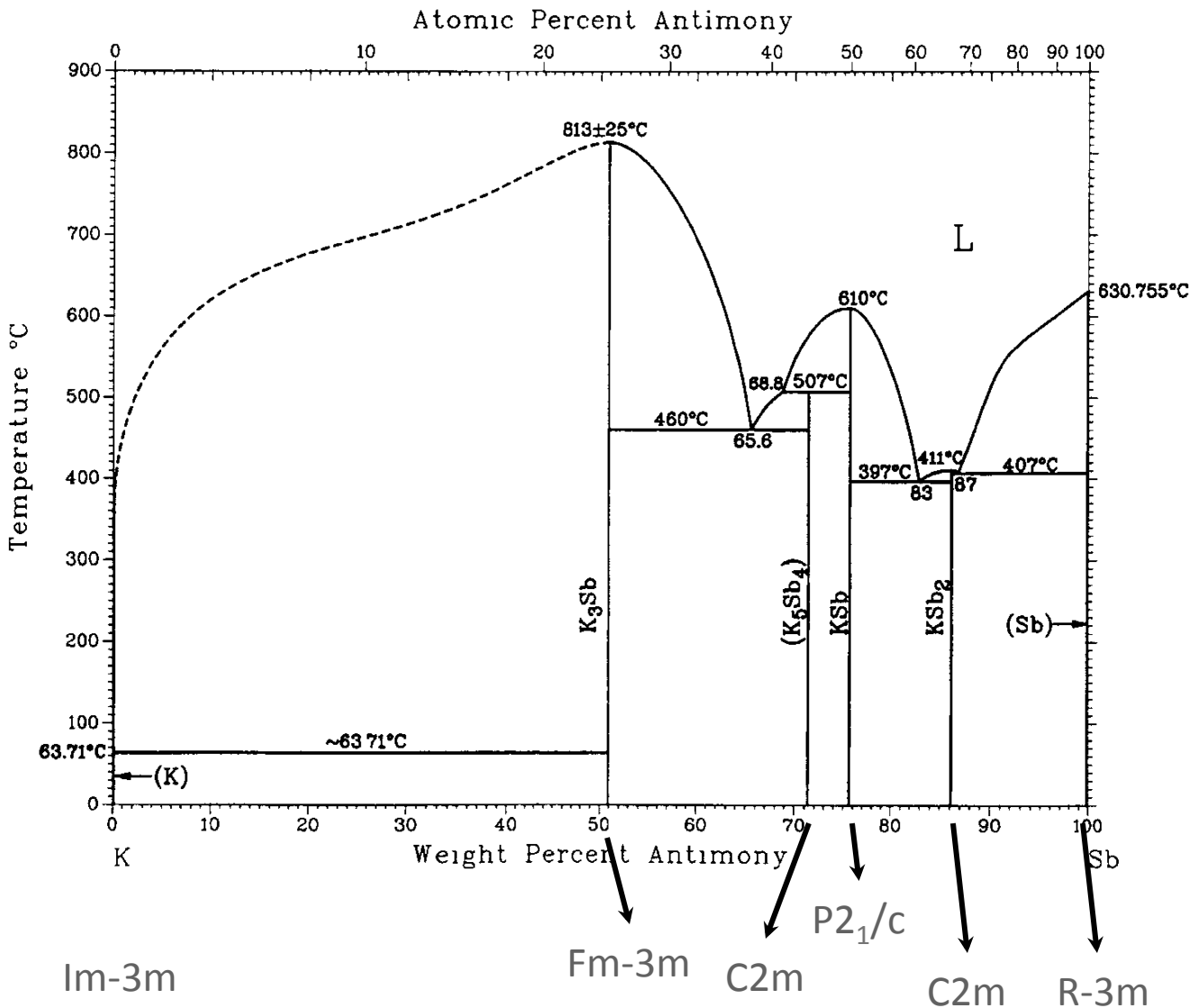
A. Lvashenko

# What Can We Learn from the Past?



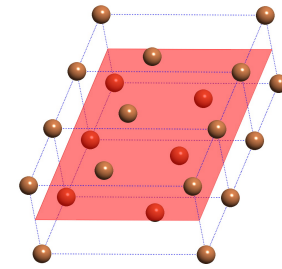
- The cathode of interest:  $CsK_2Sb$
- Recipe from different communities
  - Various recipes are available
  - Recipe includes:
    - Process timing
    - Process temperatures (and ramps)
    - Evaporator design, pump rates, details of materials.....
    - Recipe depends on evaporator system
- Groups of recipes
  - Either Co-evaporation or sequential evaporation
  - Interlayer between glass and cathode or none

# What Happens on an Atomistic Level?



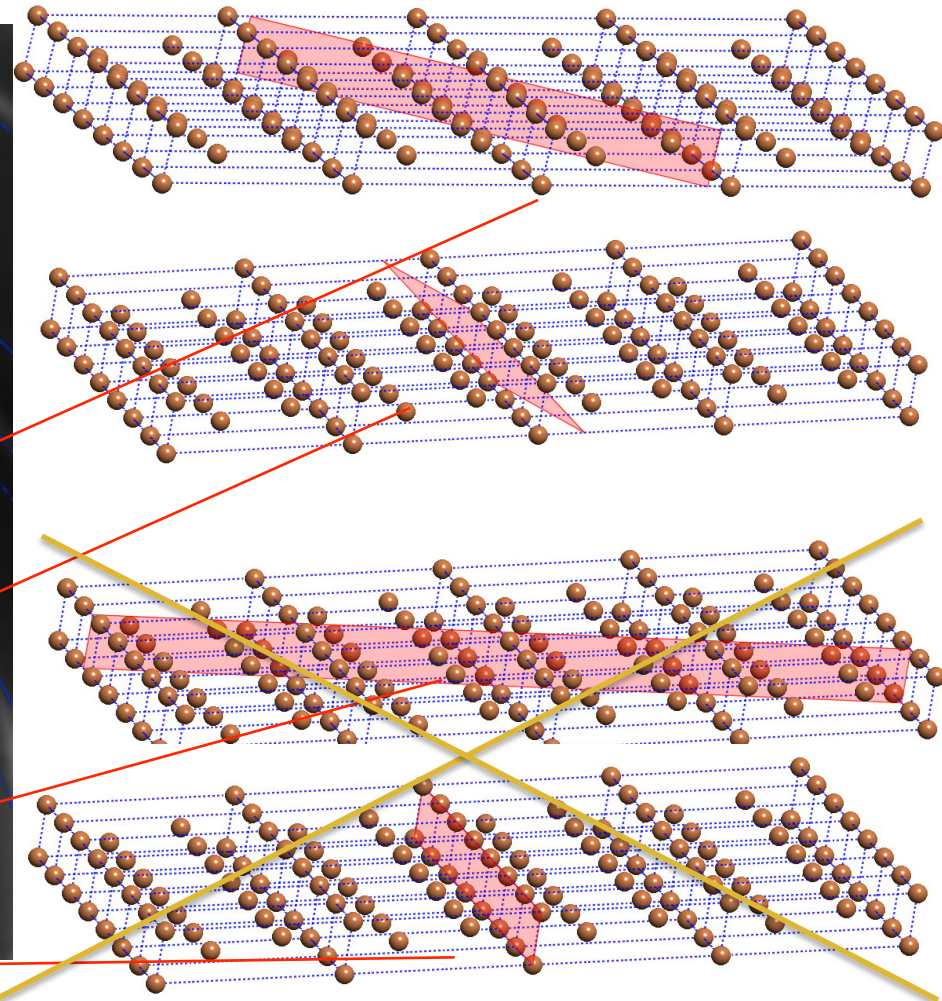
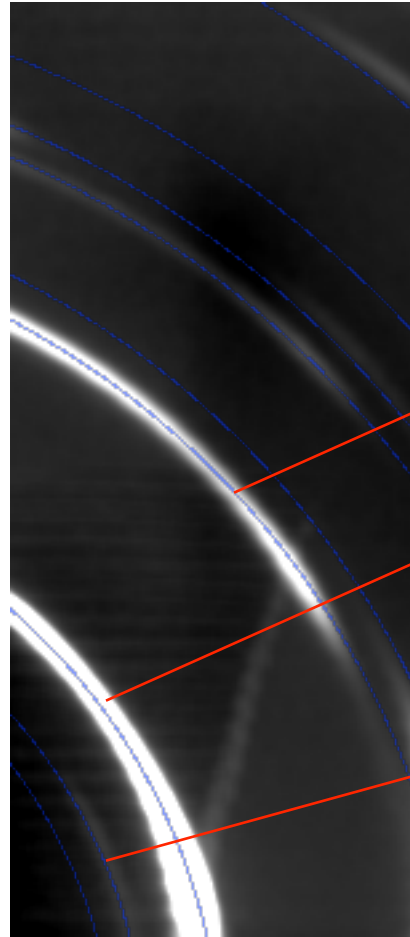
- B33 (substrate)
  - How clean is clean
  - Is there any influence of surface states
- Interlayer
  - Chemical composition
  - Roughness
  - structure
- Conversion of Sb-Metal → K<sub>3</sub>Sb
  - Influence of Sb-Metal structure on final K<sub>3</sub>Sb structure?
  - Final structure
  - Final composition
- Conversion of K<sub>3</sub>Sb → CsK<sub>2</sub>Sb
  - Same questions as above

# Pre-alignment of the Sb-layer



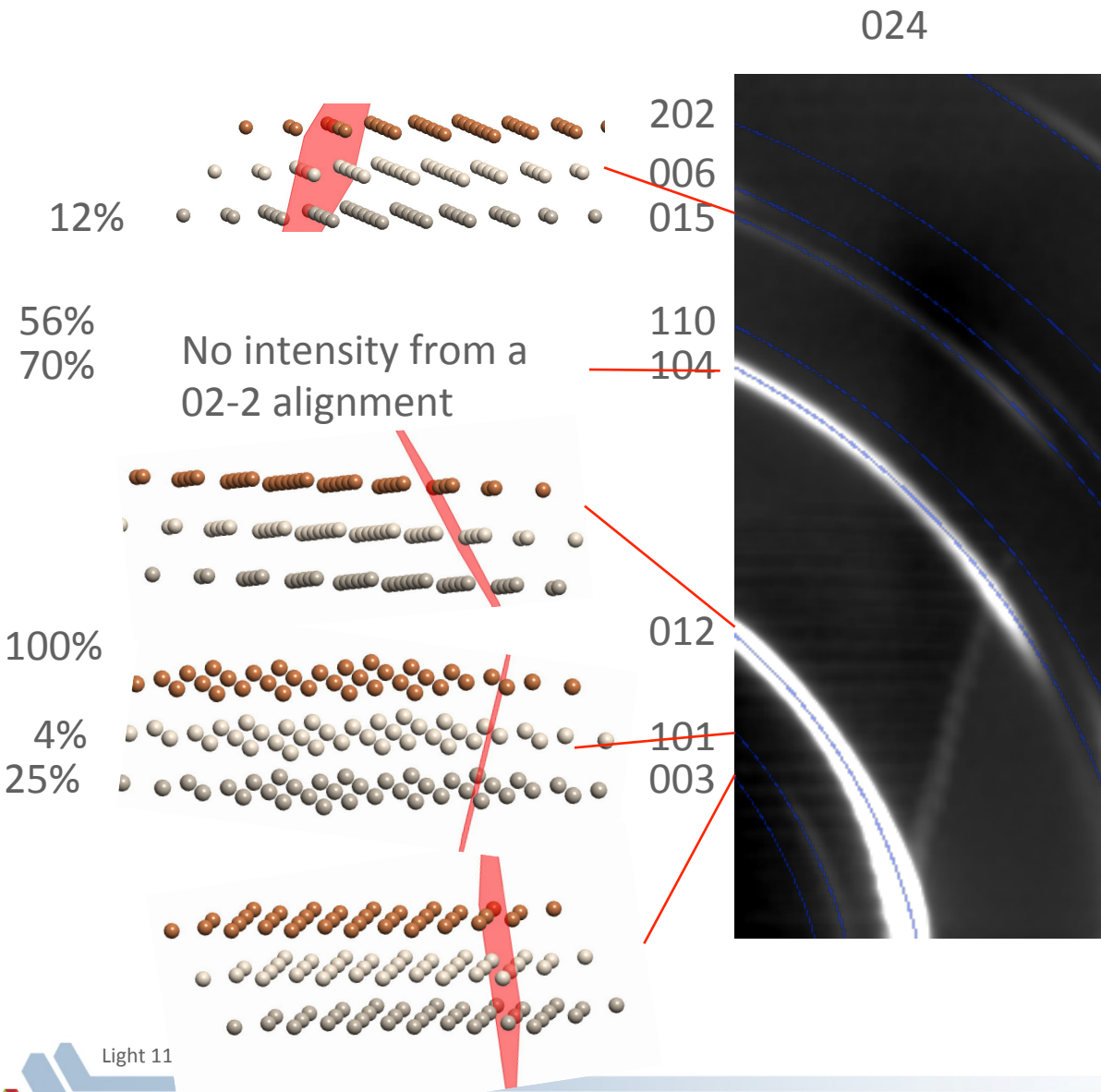
?

$2\theta$	intensity	h k l
46.99	15	0 2 4
41.00	26	2 0 2
38.55	35	0 0 6
37.49	12	0 1 5
33.48	56	1 1 0
32.01	70	1 0 4
23.00	100	0 1 2
20.18	4	1 0 1
19.02	25	0 0 3

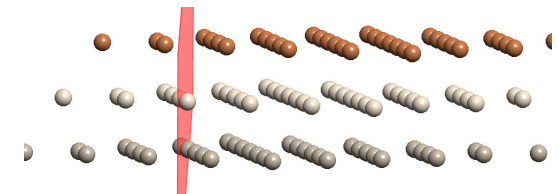


- Preliminary analysis:  
Crystallites grow with 010-plane on the substrate

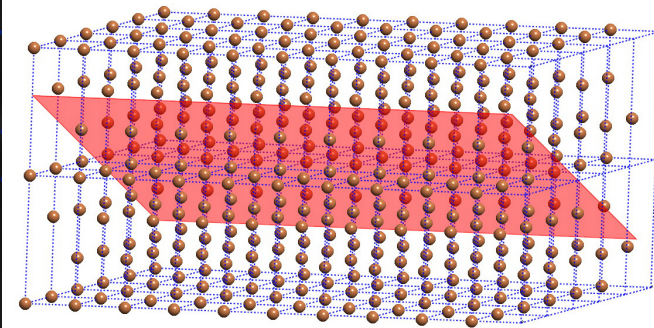
# The Sb-Film and the Substrate



104- reflection:



02-2 alignment



001 alignment

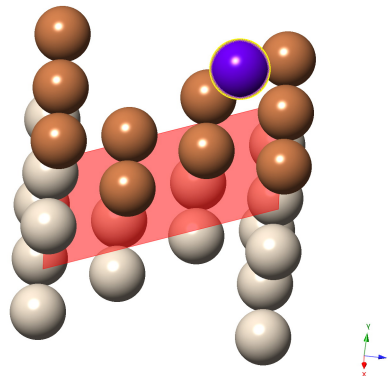
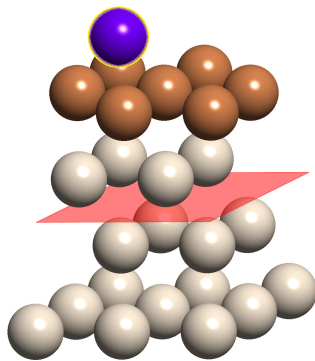
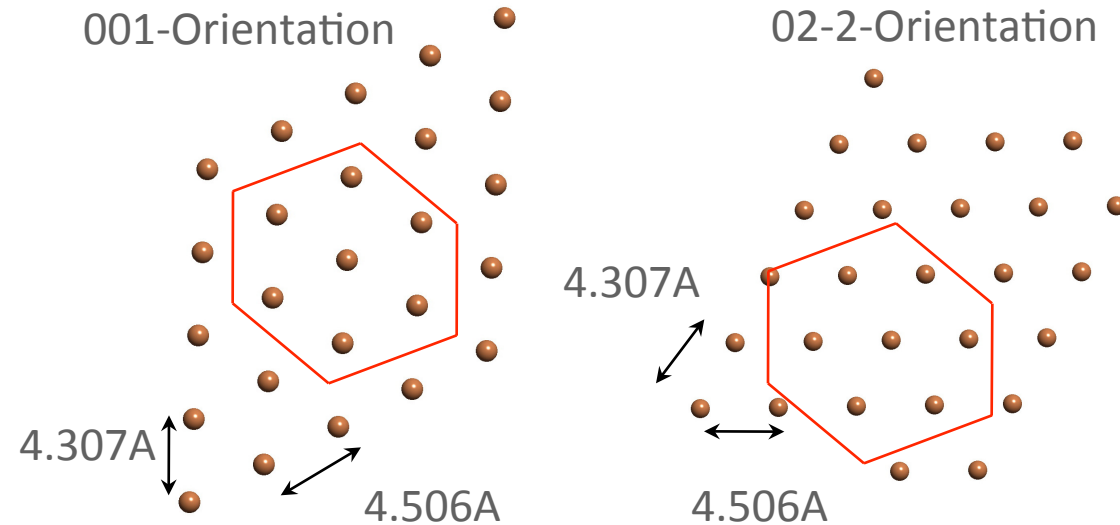
Crystal-interface is most likely a combination of 02-2 and 001 crystallites

# Some Properties of the two Crystallite Orientations

First layer between cathode and substrate:

001-Orientation

02-2-Orientation

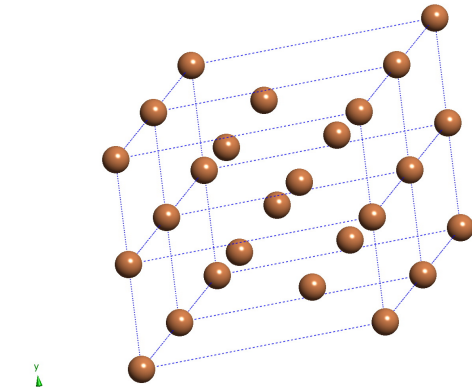


- Both crystallites give similar growth conditions
- Ionic radius of K is larger as the “open” area -> no easy inter-diffusion
- Steps may play a major role for start of inter-diffusion
- Explains initial amorphous growth (after 6nm crystalline)
- In first order:
  - substrate can not influence the growth ratio
  - Two crystallite-types determine grain boundary condition
  - Grain-boundary are important for K-inter-diffusion?

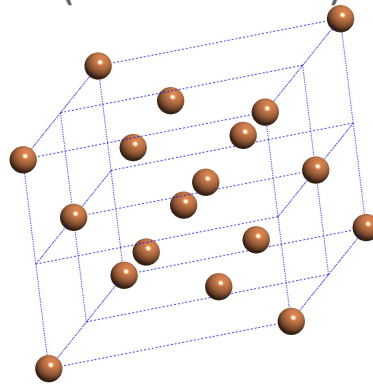


# How can you get from Sb-Metal to $K_3Sb$

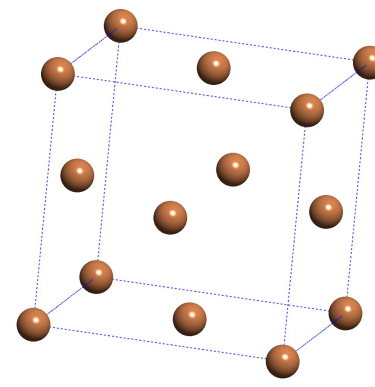
4 unit cells of Sb



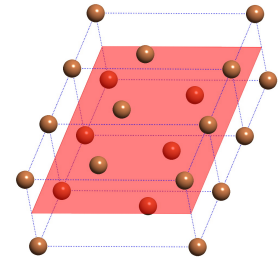
Removing 8 atoms  
(two fcc-sides)



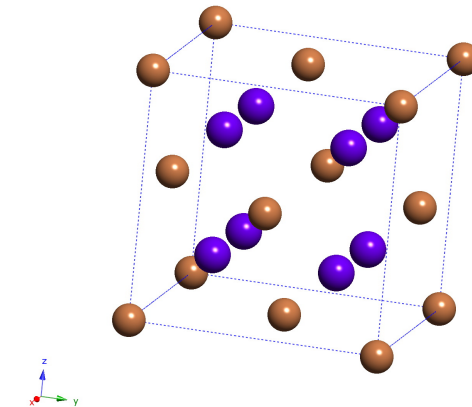
Moving the rest of the atoms  
to the FCC side



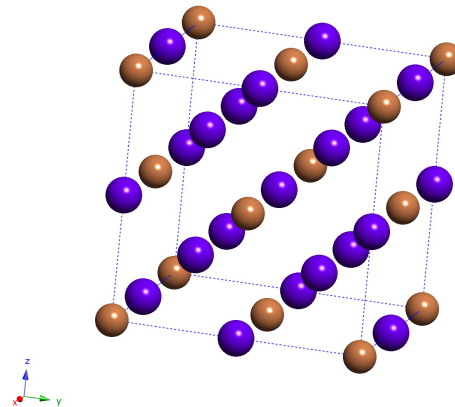
Sb-Metal surface



Filling the inner K sides



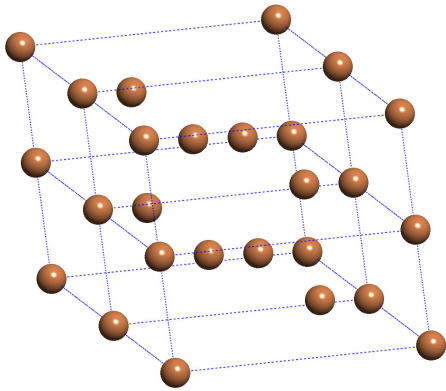
Filling the outer K sides



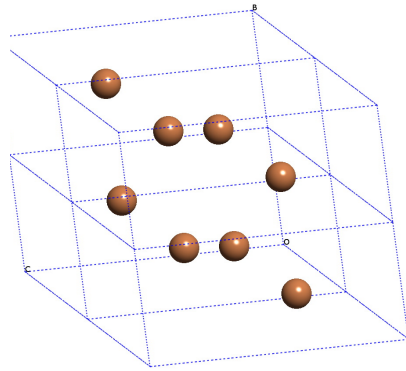
- Many Atoms have to be moved/removed
  - Not clear where they go
  - Does the film loose Sb atoms during K-Sb reaction?
- Inter diffusion of K will not be possible for all crystal planes!
- Is K-Sb bonding energy the “motor” of this transition?

# How can you get from Sb-Metal to KSb

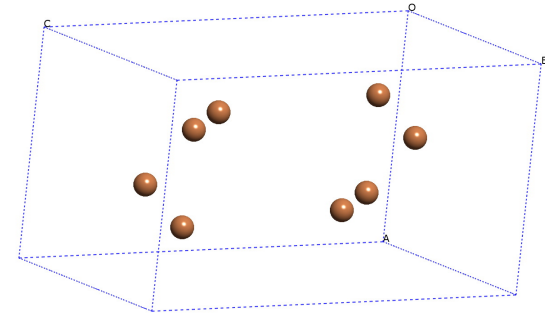
Sb-metal



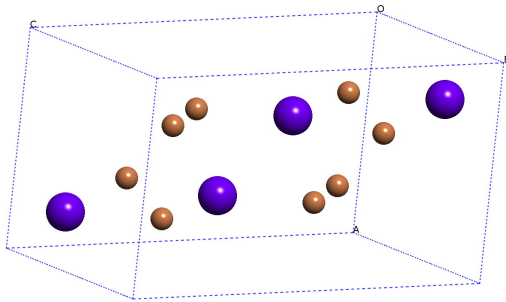
Removing of  
corner atoms



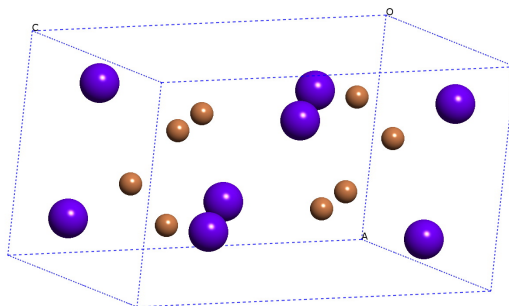
Rearranging Sb-atoms



Filling first K-position



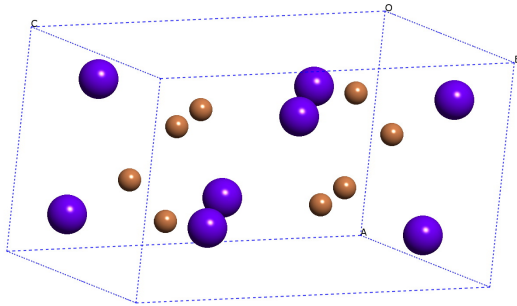
Filling second K-position



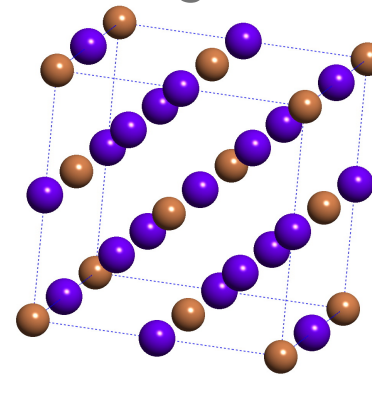
- Fewer Sb-atoms have to be removed
- Strong Sb-Sb bonds (spiral)
- K-cage holds the crystal together

# No transition between KSb and K<sub>3</sub>Sb?

KSb



K<sub>3</sub>Sb



- No Transition between KSb and K<sub>3</sub>Sb possible (wrong Sb-positions are occupied) without melting?
- Access K yields to lateral segregation not to a transition
- What drives the initial growth?

# Characterization of the Full Cathode Growth

## Sample 1

8 nm Sb deposition at 100 C  
16 nm K deposition at 100 C  
Substrate heating to 300 C  
18 nm Cs deposition at 100 C  
Substrate heating to 300 C  
8 nm Sb deposition at 100 C  
24 nm Cs deposition at 100 C  
Substrate heating to 300 C

## Sample 2

16 nm Sb deposition at 30 C  
63 nm K deposition at 100 C  
Substrate heating to 300 C  
16 nm Sb deposition at 100 C  
40 nm Cs deposition at 100 C  
Substrate heating to 300 C

Sample	Total Sb	Total K	Total Cs
Sample 1	16nm	16nm	42nm
Sample 2	32nm	63nm	40nm

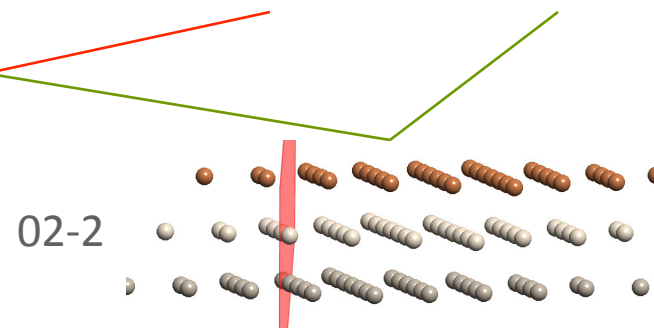
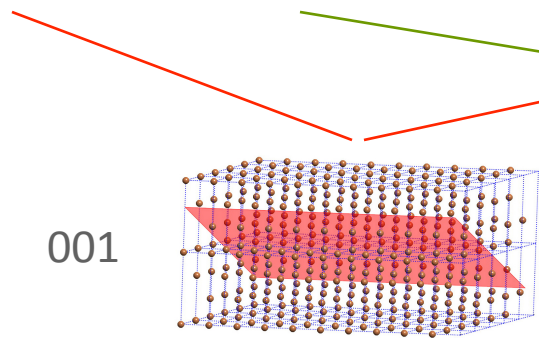
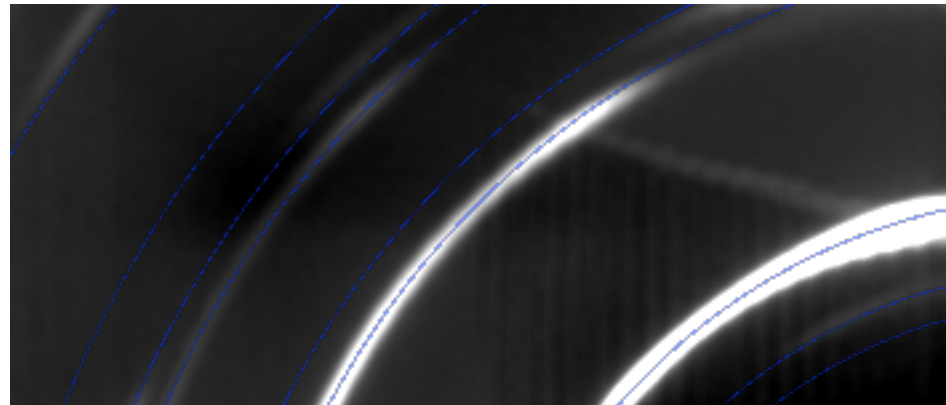
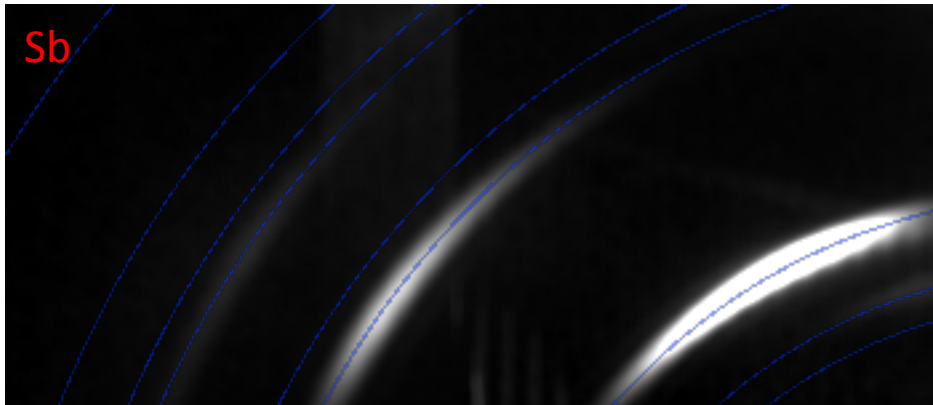
- Growth temperature of Sb-film
- Sequence of growth
- Total thickness

# Initial Sb-Film

Thickness	8nm	16nm
Temperature	30C	100C

Sample 1

Sample 2

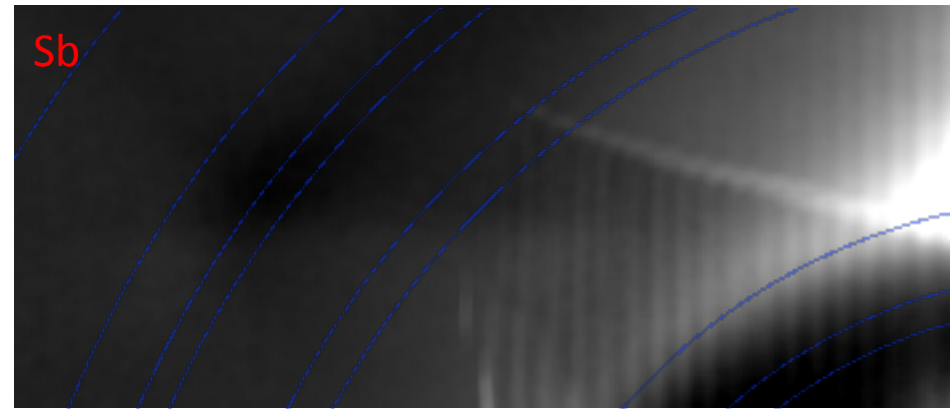
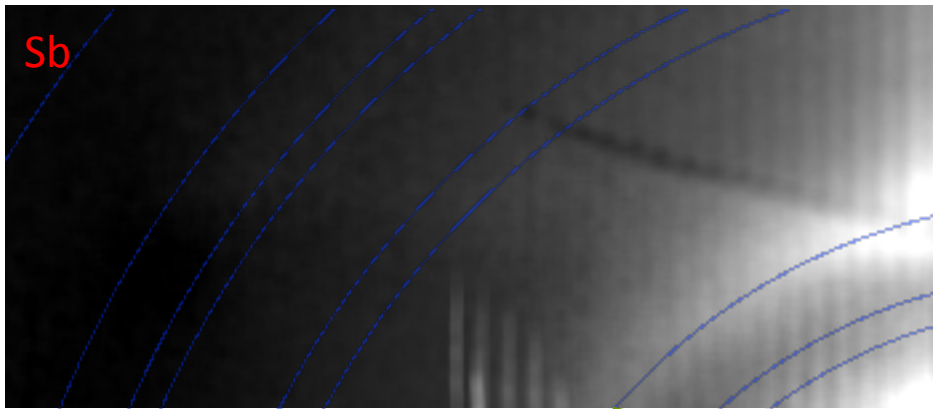


# First K-deposition

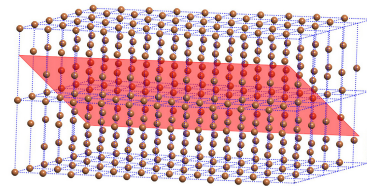
Thickness	Sb 8nm/ K 16nm	Sb 16nm / K 63nm
Temperature	100C	100C

Sample 1

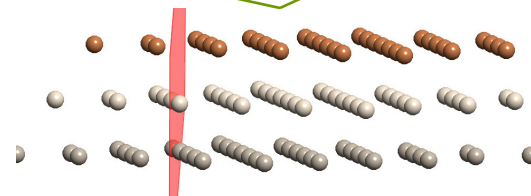
Sample 2



Reacted 001



02-2

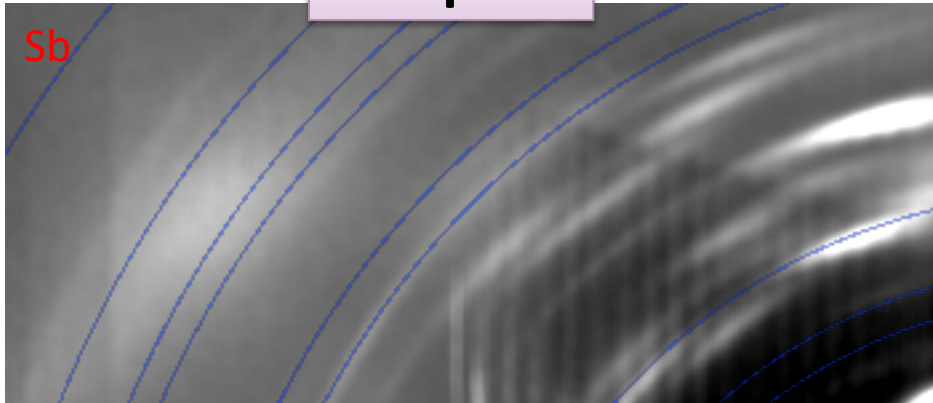


Not reacted?  
Strongly strained  
A specific  
orientation  
survived

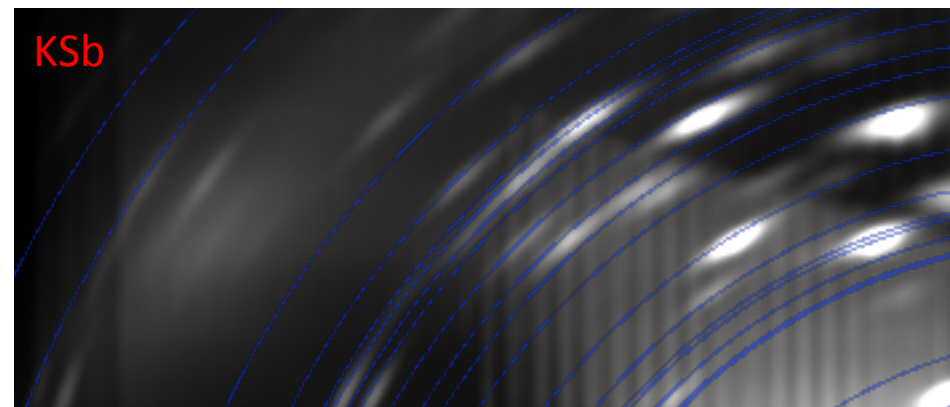
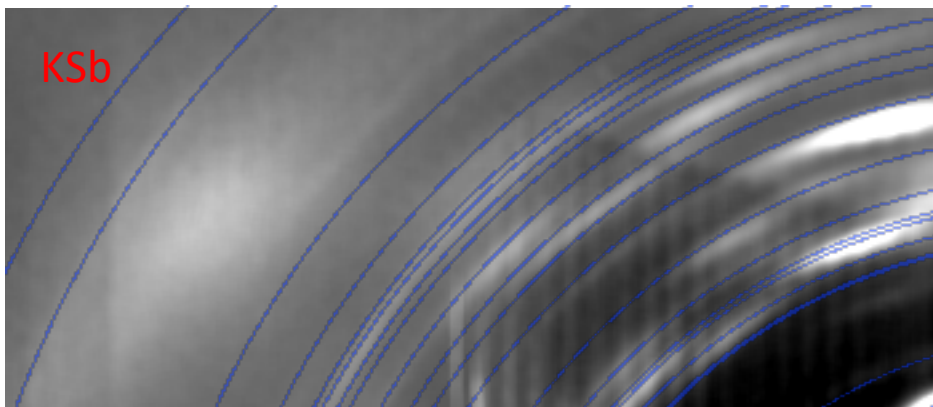
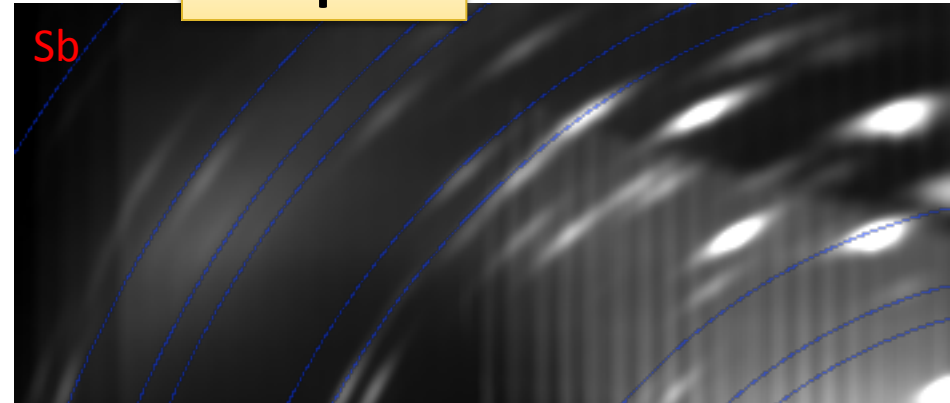
# Annealing of KSb-Compound at 300C

Thickness	Sb 8nm/ K 16nm	Sb 16nm / K 63nm
Annealing Temperature	300C	300C

**Sample 1**



**Sample 2**



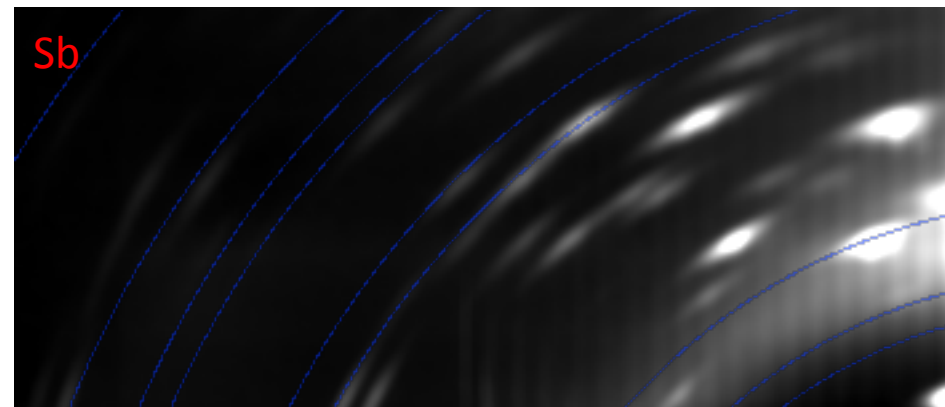
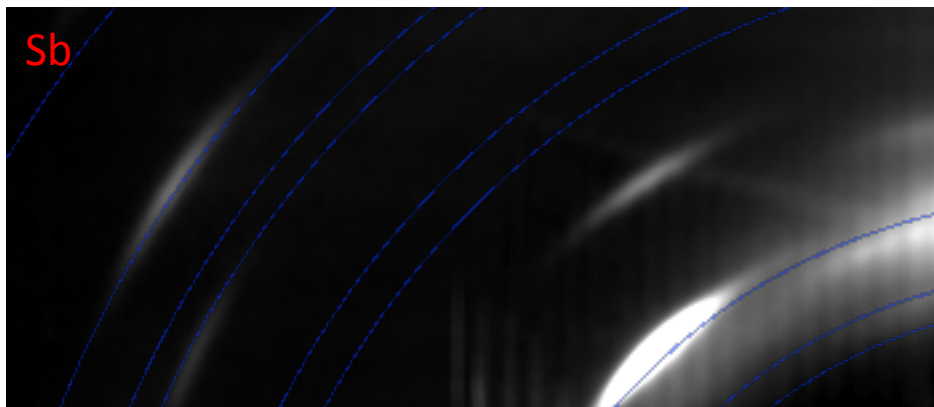
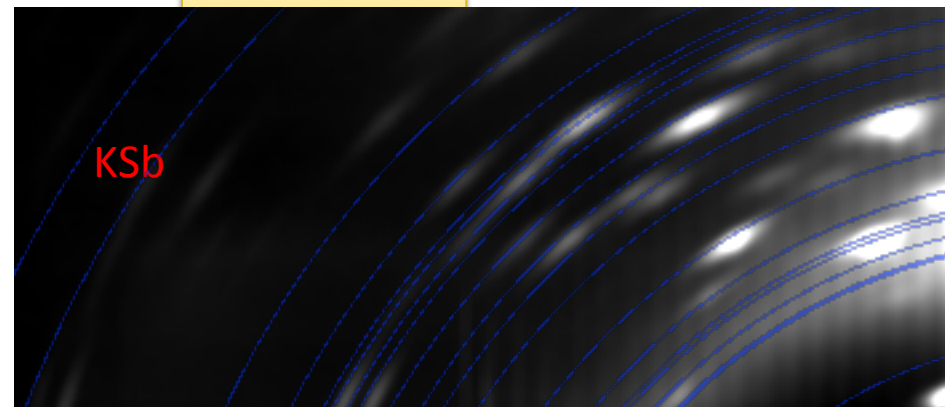
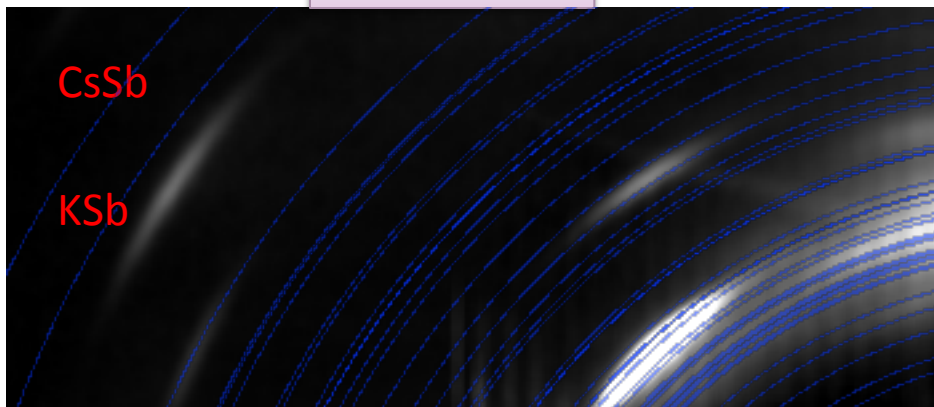
- KSb in both cases (independent from K-thick.); some systematic deviation (strain/vacancies?)
- Very strong texturing for sample 2
- May be Sb-metal phase (001-phase)

# Cs-Deposition

Thickness	Sb 8nm/ K 16nm /18nm	Sb 16nm / K 63nm/ Sb 16nm / 40nm Cs
Annealing Temperature	100C	100C

**Sample 1**

**Sample 2**



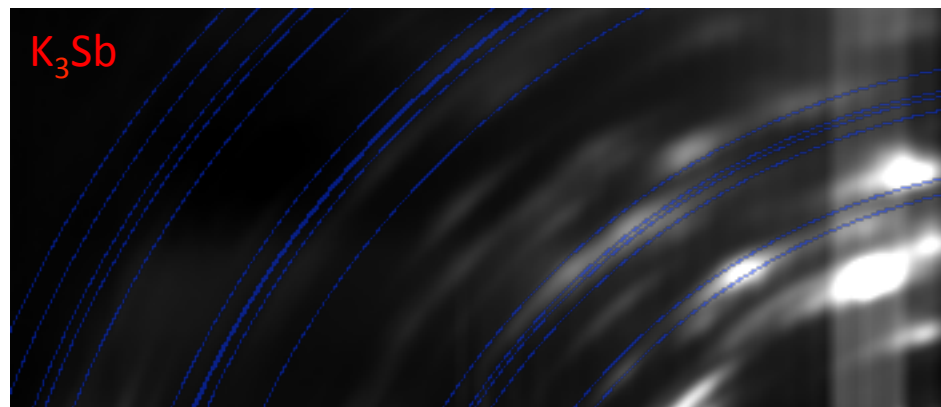
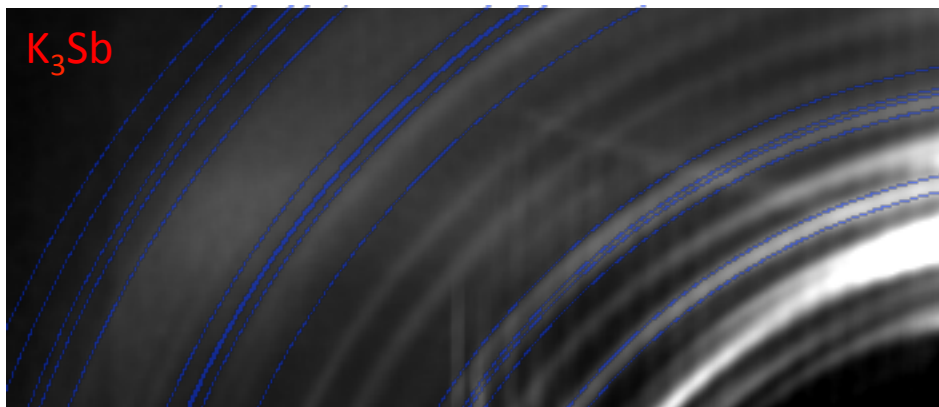
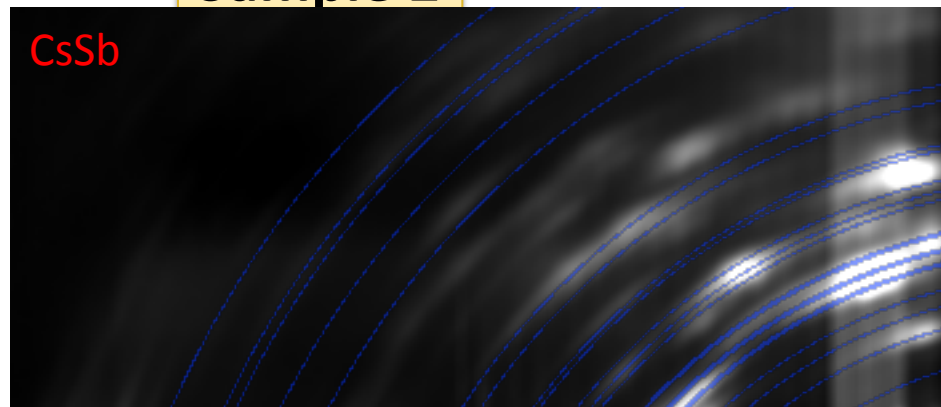
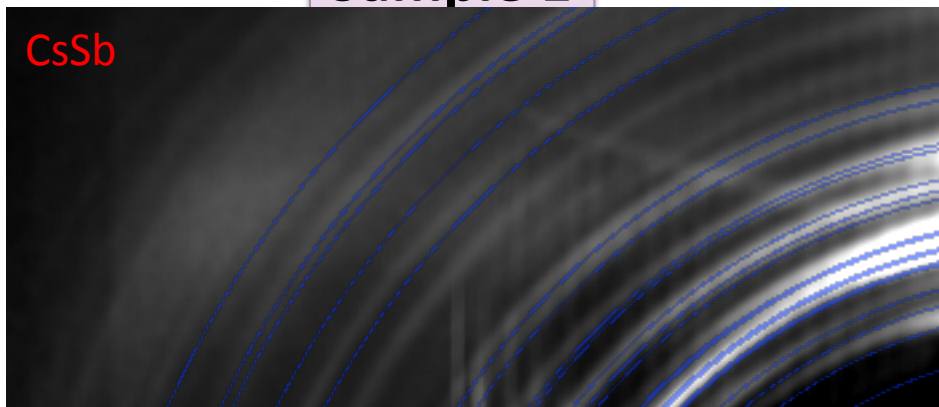
- Some metallic Sb left in both cases
- No crystalline phase of alkali-Sb for sample 1
- KSb phase visible for Sample 2



# Annealing of CsKsSb-Compound at 300C

Thickness	Sb 8nm/ K 16nm /18nm	Sb 16nm / K 63nm/ Sb 16nm / 40nm Cs
Annealing Temperature	300C	300C

**Sample 1** **Sample 2**

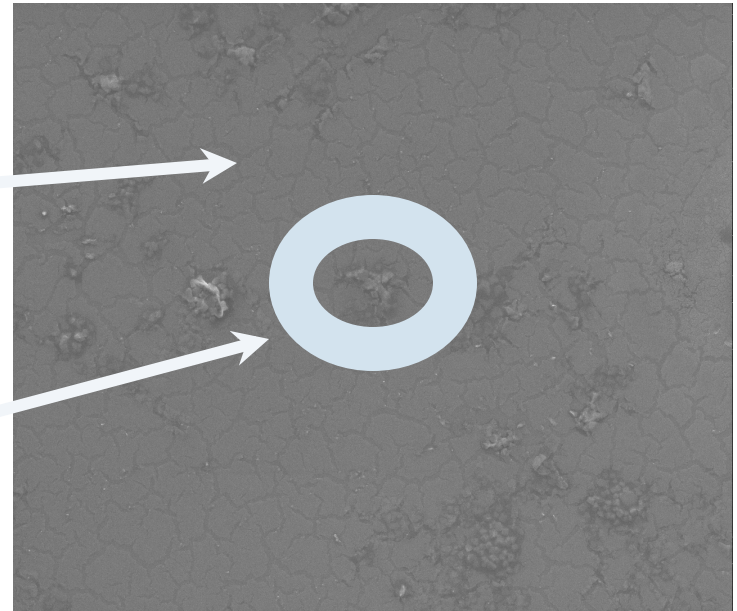


- In both cases mixture of AlSb (Al=Cs/K)
- Unlikely a Al<sub>3</sub>K-phase! (Al=Cs/K)

# Summary of In-situ Growth Experiment

Sb K Cs on Si X21 Oct 2011 Samp 3 1 Date:10/5/2011 4:31:31 PM HV:15.0kV Puls th.: 17.27kcps Center Average

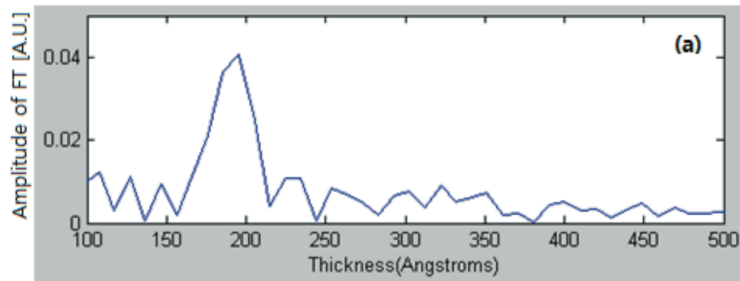
El	AN	Series	unn. C [wt.%]	norm. C [wt.%]	Atom. C [at.%]	Error [%]
C	6	K-series	0.54	0.56	1.35	0.9
O	8	K-series	3.69	3.85	6.90	1.1
Si	14	K-series	84.15	87.79	89.71	3.5
K	19	K-series	0.52	0.54	0.40	0.1
Sb	51	L-series	3.88	4.05	0.96	0.6
Cs	55	L-series	3.08	3.21	0.69	0.3
Total:			95.86	100.00	100.00	



- Observations: Very K-rich (K-metal?)
  - Sb-metal film growth often strongly textured
  - K-evaporation onto of Sb-metal yield to an amorphous material or glass (no long range order)
  - Formation of islands are unlikely since this would favorite crystalline phases which cannot be detected!
  - K-Sb mixture crystallizes at 300C (dynamics, activation energies are currently not known but can be extracted from existing data set)
  - Crystallized K-Sb film is mainly KSb with strong texturing (orientation and crystal size can be concluded from existing data set)
  - Cs behaves very similar to K
  - Produced cathode was not homogeneous: largely a CsSb-phase and a crystalline non identified CsKSb-phase

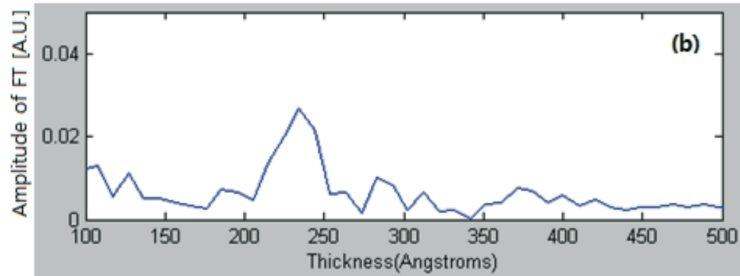
# The Transition from Sb-Film to $K_3Sb$ -film

## Surface Roughness during the Processing



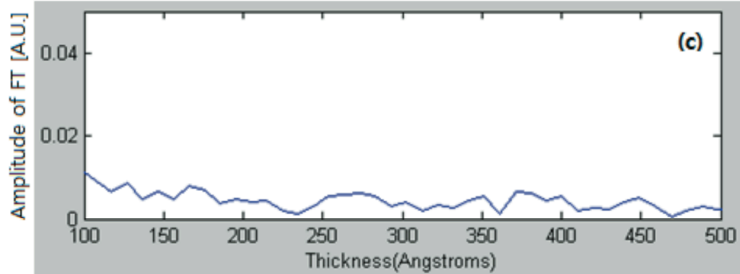
Sb-Metal

- Nice smooth film with 19nm thickness
- Height distribution  $\sim 3$ nm



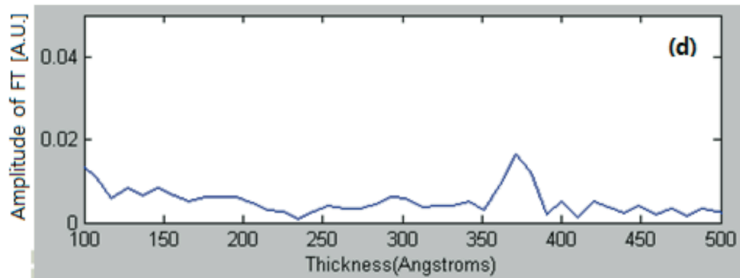
K-evaporation started

- Decrease of peak height indicates fraction of surface don't contribute to signal
- Height distribution  $\sim 5-7$ nm
- No double layer structure



K-evaporation ended

- No reflectivity signal detectable
- Very rough!



heating

- Reflectivity signal comes back
- Not all surface has recovered
- Goes ahead with crystallization!

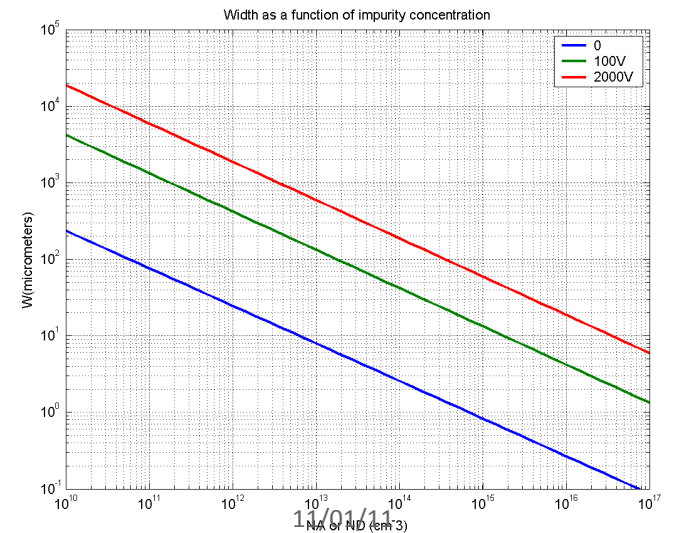
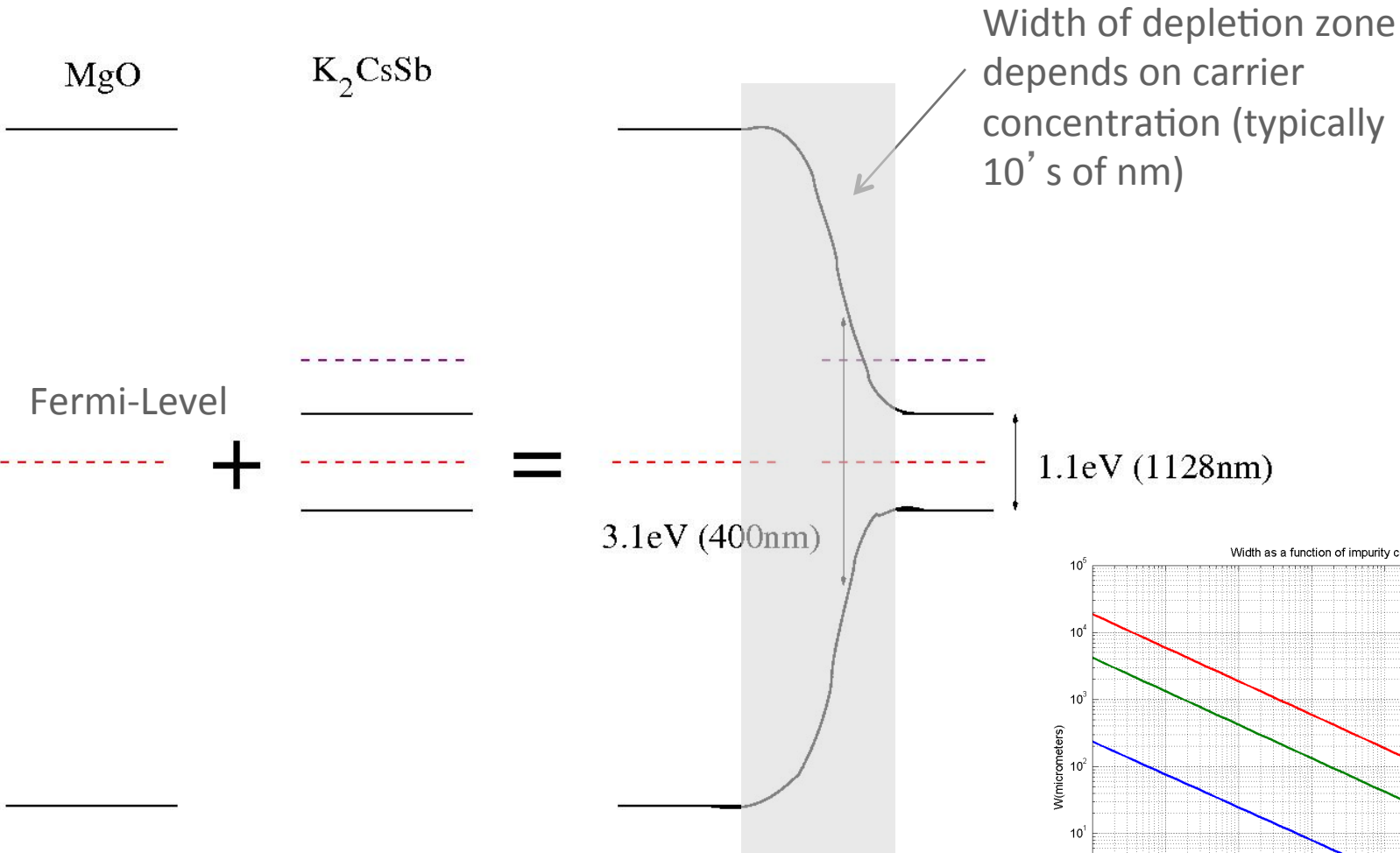
# Influence of Interface Layer

- Commonly used materials:

Material	Crystal group	Lattice parameter	Match with $K_3Sb$	Band gap
$Sb_2O_3$	Fd-3m	$a=11.152\text{\AA}$	yes	3.7-3.9eV
$Sb_2O_4$	Fd-3m	$a=10.26\text{\AA}$	yes	?
MgO	Fm-3m	$a=4.2117\text{\AA}$	excellent	4.7-7.8eV
BeO	$P6_3mc$	$a=2.698\text{\AA}$ $c=4.3772\text{\AA}$	no	10.7eV
$K_3Sb$	F m -3 m	$a=8.493$		1.4eV
$CsK_2Sb$	F m -3 m	$a=8.61$		1.0-1.2eV

**BeO is used to produce super-bialkali cathodes!**

# Combining Wide-Band-Gap Materials with Alkali Systems



# The Next Steps

- Instrumentation:
  - Development of miniature evaporator system with defined growth conditions (high q-range, easy to transport, can be implemented in various beamlines)
  - Data-quality improvement: calibration standard & background reduction
- Data-analysis, simulation, & theory:
  - Automatic data analysis using script languages
  - Quantitative analysis of texture information
  - Peak-width simulation based on strain, size and defect-structure
  - Data base for known compounds (alkali-Sb and oxides/fluorids)
  - Calculation of potential surface for Alkali inter diffusion (at least important areas)
- Program:
  - Influence of Oxide layer on growth and band bending
  - Understanding of KSb versus  $K_3Sb$  growth

# Conclusion

- In-situ X-ray diffraction and reflectivity was applied and provides:
  - Compound composition during the processing
  - Structural information on crystallinity, size and orientation of crystals
  - Temporal evolution of these parameters
- Results of the presented experiment:
  - Alkali-evaporation at 100C substrate temperature yields to amorphous or glassy material
  - No transversal but lateral segregation is observed.
  - Crystallization can be achieved at 300C heating (necessary time can be extracted from data)
  - Grown cathode is more of the CsSb and some non-identified CsKSb-compound (not CsK<sub>2</sub>Sb)
  - Crystallinity (and texture) of the final film is independent from the Sb-structure but may depend on the KSb-crystallinity and the influence of the substrate layer?
- Next goals
  - Improve in-situ experiment so that many cathode recipes can be investigated.
  - Influence of the substrate on the crystallization process of the Alkali compound
  - Determination of activation energies and rate constants of the crystallization process (for the different compounds).